

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application Serial No. .... 10/813,543  
Filing Date ..... March 30, 2004  
Confirmation No. .... 8087  
Inventor ..... Gealy, F. Daniel  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 1792  
Examiner ..... Keath T. Chen  
Attorney's Docket No. .... MI22-3685  
Title: ..... Method for Reducing Physisorption During Atomic Layer Deposition

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References - - See attached Form PTO/SB/08a

The attached Form PTO/SB/08a is submitted in compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, and your attention is directed to the reference listed on the attached Form PTO/SB/08. No admission is made regarding whether the submitted reference is prior art.


This Supplemental Information Disclosure Statement is being filed with a Request for Continued Examination. Therefore, no fee is believed to be required. However, in the event that a fee is required for filing this Supplemental Information Disclosure Statement, please charge the fee specified under 37 C.F.R. § 1.17(p) to Deposit Account No. 23-0925.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 10/31/08

By: \_\_\_\_\_

  
Robert C. Hyta  
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